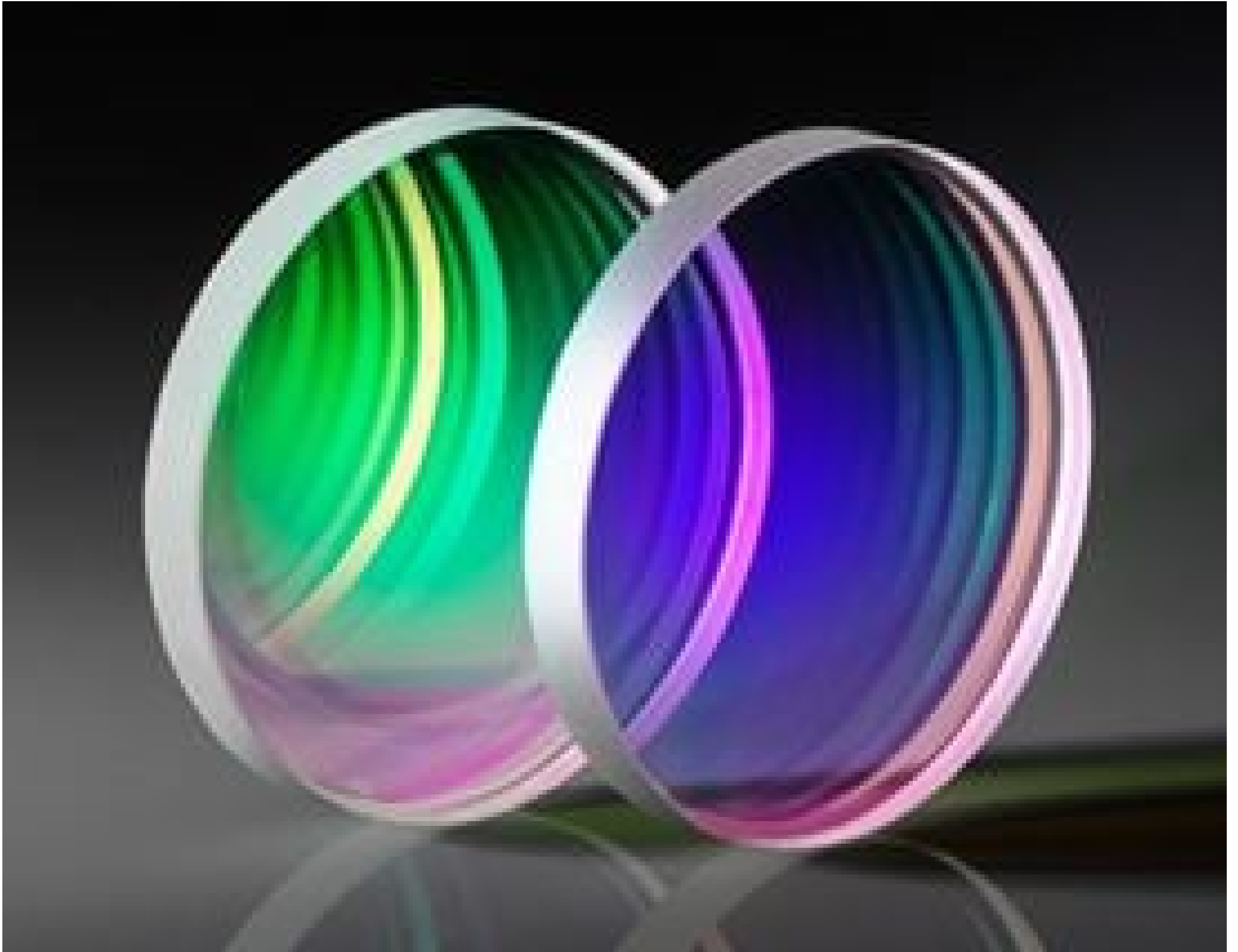


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10-25nm, 50.8mm Dia, EUV/IR Dichroic Filter



Extreme Ultraviolet (EUV) Dichroic Filters

Stock **#18-279** **3 In Stock**

1 MRP ₹5,44,806

Price inclusive of all taxes

ADD TO CART

Volume Pricing

Qty 1+	₹5,44,806 each
Need More?	Request Quote

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General

Dichroic Filter **Type:**

Physical & Mechanical Properties

50.80 **Diameter (mm):**

5.08 ±0.1 **Thickness (mm):**

<5 **Parallelism (arcmin):**

Dimensional Tolerance (mm):

+0.0/-0.2

Optical Properties

78 **Angle of Incidence (°):**

Fused Silica (Corning 7980) **Substrate:**

Dielectric Multilayer AR **Coating:**

>35 **Reflection (%):**

20-10 **Surface Quality:**

10 - 25 **Wavelength Range (nm):**

<N10 @ 633nm **Surface Figure, RMS:**

Regulatory Compliance

[View](#) **Certificate of Conformance:**

Japan **Country of Origin:**

Imported By:
Edmund Optics India Private Limited
267, Greystone Building, Second Floor,
6th Cross Rd, Binnamangala,
Stage 1, Indiranagar, Bengaluru,
Karnataka, India 560038
Phone: +91- 80-6845 0000

Product Details

- Separates EUV from the NIR Laser Source in High Harmonic Generation
- Designed for High Damage Thresholds
- Supports Applications from 10 – 40nm
- Available from Stock
- No Minimum Order Quantities, No Coating Lot Charges

Extreme Ultraviolet (EUV) Dichroic Filters, also known as beam separators, are intended for high harmonic generation applications by providing a high separation efficiency between the EUV and NIR wavelengths. Featuring a Fused Silica substrate, these filters support higher laser powers than the alternative Brewster's angle beam separators and EUV filters. EUV Dichroic Filters feature a broad bandwidth range from 10nm to 40nm. In addition to high harmonic generation, these filters can also be used in systems that support EUV applications such as EUV lithography, EUV nanomachining, coherent diffractive imaging, and ultrafast attosecond pulse generation.